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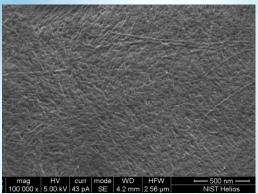
 mag
 HV
 curr
 mode
 WD
 HFW
 ⊷
 500 nm
 ⊷

 100 000 x
 5.00 kV
 43 pA
 SE
 4.2 mm
 2.56 μm
 NIST Helios

NIST is the nations measurement and standards laboratory

Research in nanotechnology and the needed nanometrology is found all across NIST

Work on dimensional metrology of CNCs began in 2006-7 with an early paper and presentation in 2008 employing SEM, HIM and AFM



- Leverages the knowledge gained from work on other nanomaterials
- Requirement for both basic (research and laboratory) and manufacturing (production) metrology.

- Challenges in Characterizing Small Particles: Exploring Particles from Nano- to Microscale National Research Council. National Research Council. 2012
- **Special "Green" Materials Forum** SPIE Instrumentation, Metrology, and Standards for Nanomanufacturing, Optics, and Semiconductors.2011
- Cross-Industry Issues in Nanomanufacturing NNI/NIST Sponsored Workshop - A NNI/NIST Sponsored Workshop May, 2008.
- Interagency Working Group Instrumentation Metrology and Standards for Nanomanufacturing Workshop, Gaithersburg, MD (October 17-19, 2006)
- NNI Interagency Grand Challenge Workshop on Instrumentation and Metrology. January 27-29, 2004.

- NEED: Measurement instrument validation standards and procedures
 - Calibration
 - Chemical Composition
 - 3-D Physical Properties
 - Size/Length, Strength, etc.
 - Misuse of standards
 - Standards are often developed for a specific use
 - Use for other purposes can invalidate them
 - latex spheres
- NEED: Standardized measurement
 procedures
 - Do instruments of the same class provide the same answers to the question: "How XXX* is it"
 - Interlab Study data from the same lab

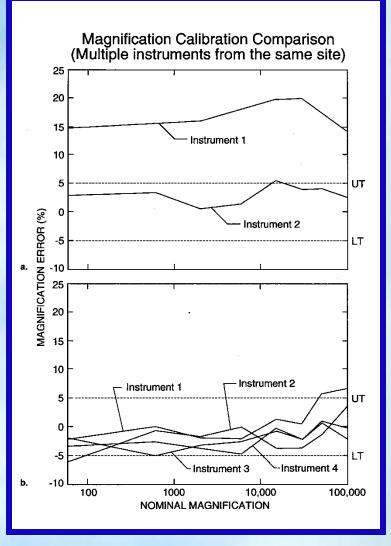
XXX*- fill in the blank: big, composition, etc.

Instrument Calibration: Interlaboratory SEM Study

- Over 60 instruments studied
- Calibration error varied between 10 % and 60 %.
- "X" scan to the "Y" scan was not 1:1
- Gross differences in data from instruments from the same laboratory

Reference:

Postek, M. T., Vladar, A. E., Jones, S. and Keery, W. J. 1993. Inter-laboratory study on the lithographically produced scanning electron microscope magnification standard prototype. NIST J. Res. 98:447-467.



- NEED: Fundamental, scientifically validated, material property measurement databases.
 - National labs have been a good source for this type of work
 - NIST, Sandia, Oak Ridge
 - Needed for input into a variety of predictive models
 - Accurate models can answer many questions economically:
 - EX: What is the proper loading of CNC to achieve a particular strength?
 - EX: What would happen if a different resin is used? Accurate models can result in tremendous savings to industry

NEED: Performance standards and procedures

- Characterizing nanomaterials requires the instruments to function optimally at all times
 - Need to know how well an instrument <u>should</u> run and monitor that performance (or lack of it)
 - Does the instrument performance change with time?
 - When is maintenance needed
- NEED: New methods for imaging and characterization need to be developed
 - Helium ion microscope

- NEED: Fundamental understanding of methods divergence and 3-D hybrid metrology issues:
 - Use the right tool for the right purpose
 - Why different types of instruments provide different answers.
 - EX: Gold nanoparticle standard

Table 1. Reference Value Mean Size and Expanded Uncertainty ^(a) Average Particle Size (Diameter), in nm

Particle Size (nm)	
±	0.3
) <u>+</u>	0.1
) <u>+</u>	0.1
±	0.1
5 <u>+</u>	0.1
<u>+</u>	1.8
5 9 3 5	$5 \pm 9 \pm 9 \pm 3 \pm 5 \pm 100$

- Why is methods divergence a big problem?
 - Multiple studies using different instruments reporting different data
- Reasons for methods divergence
 - Instrument issues:
 - SEM electron beam interaction
 - Optics diffraction
 - Scanned probe tip size
 - Etc.
 - Sampling differences
 - Not all techniques measure the same measurand
 - Need to know what you are measuring, how it is being measured and why it is being measured.
 - What is the role of accuracy?

- NEED: Manufacturing Metrology
 - How do you characterize a boatload of nanomaterials with no or little human intervention with high throughput?
 - What automated equipment will be needed?
 - Instrument manufacturers need to be directed and put into the loop early
 - ITRS
 - Semiconductor industry a good example but it has taken a long time and much investments in R&D
 - Knowledge can be leveraged

Conclusion

 In the nanoworld, we have no first-hand experience so we must rely on "well calibrated" instruments to provide measurements for any conclusions.

Instruments are fallible

- Role of accurate measurements more important today than any other time because the error budget is so small and we cannot rely only on past data since properties might change
- Metrology is often the last thing considered, but often turns out to be a limiting factor.
 If you can't measure it, you can't manufacture it

Thank you